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PATENT & TRADEMARK OFFICE

AF/2800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#24/F
11-17-02
Clayton

In re Application of:
Rathi, et al

Serial No.: 09/165,248

Confirmation No.: 7619

Filed: October 1, 1998

For: A Silicon Carbide Deposition for Use as a Barrier Layer and an Etch Stop

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§ Group Art Unit: 2823
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§ Examiner: G. R. Fourson III
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Box AF
Assistant Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING
37 CFR 1.8
I hereby certify that this correspondence is being deposited on 11/05, 2002 with the United States Postal Service as First Class Mail in an envelope addressed to: Box AF, Commissioner for Patents, Washington, D.C. 20231.

11/05/02 — Date
Signature

Dear Sir:

RESPONSE FINAL TO OFFICE ACTION DATED SEPTEMBER 5, 2002

In response to the Final Office Action dated September 5, 2002, having a shortened statutory period for response set to expire on December 5, 2002, Applicant requests entry and consideration of the following amendments and remarks. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/2966/DSM/BCVD/JD, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE CLAIMS:

Please cancel claims 1-8, 10-13, and 28 without prejudice, and amend the claims as follows:

1. (Cancelled) A method for processing a substrate, comprising: